

# Papers by Bell Laboratories Authors

## CHEMISTRY

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**Investigation of the Ti-Pt Diffusion Barrier for Gold Beam Lead on Aluminum.** S. P. Murarka, H. J. Levinstein, I. Blech, T. T. Sheng, and M. H. Read, *J. Electrochem. Soc.*, **125** (January 1978), pp. 156-162.

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**Effect of Interfacial Reactions on the Electrical Characteristics of Metal Semiconductor Contacts.** E. H. Nicollian and A. K. Sinha, *Electrochem. Soc. Monograph Thin Films—Interdiffusion and Reactions*, New York: John Wiley & Sons (May 1978), pp. 481-531.

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**Interatomic Internal Photoemission Peaks in (Auger) Electron Spectra.** C. C. Chang, *J. Electron. Spectros. Relat. Phenom.*, **13** (1978), pp. 255-261.

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## MATERIALS SCIENCE AND ENGINEERING

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